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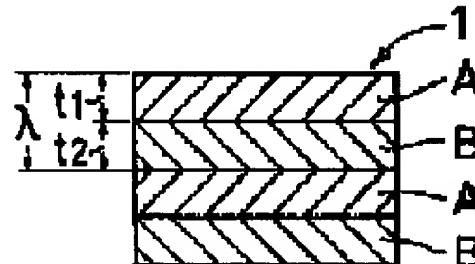
**(54) ULTRA-THIN FILM
LAMINATE**

(57) Abstract:

PURPOSE: To improve the wear resistance and oxidation resistance of the surface of a substrate by alternately repetitively laminating thin films of two kinds of Ti-Al-N compds. varying in compsn. on the surface of the substrate.

CONSTITUTION: The thin film 3 which consists of carbides, nitride and carbonitrides of group IVa, Va and VIa metals in periodic table and has a thickness of 0.05 to 5 μ m is formed by an ion plating method by a vacuum arc discharge on the surface of the hard base material 2, such as cutting tip, drill or end mill, consisting of a WC-base sintered hard a way, cermet, ceramics or high-speed steel. Two kinds of the compds. A, B expressed by $TixAl_1-xN$ (where $0 \leq X < 0.5$) and $TiyAl_1-yN$

(where $0.5 < y \leq 1$) are alternately laminated in many layers on the surface of the thin-film layer 3 by setting the sum λ of the thickness t_1 , t_2 of these compds. as a repetitive lamination period of 0.5 to 20nm. The thin films 1 having the total thickness of 0.5 to 10 μ m are thus formed. The wear resistance and oxidation resistance of the substrate 1 are greatly improved by the alternately laminated thin films of the Ti-Al-N alloy.



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